

# An Analysis and Modeling of CMOS Inverter using Vdsm

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## ABSTRACT

*A new compact physics-based Alpha-Power Law CMOS Model is introduced to alter projections of low power, space and delay circuit performance for future generations of technology. Input buffer circuits square measure utilized in a large sort of digital applications (E.g. Memory devices).The CMOS buffering circuit with the mix of resistors and capacitors square measure enforced. This mix offers higher result than in ancient CMOS style. Comparison of the traditional buffer and this planned CMOS buffer on power dissipation and propagation delay performance at completely different technologies. This approach reduces the facility dissipation effectively by moving towards low technology nodes. During this approach, the MOS devices square measure used, those MOS devices have correct and economical turning on/off characteristic by exploitation arrangement of resistors and capacitors. For mitigating the facility dissipation in scaled devices, a reliable escape Reduction Low Power Transmission Gate (LPTG) approach and tested it on Complementary Metal compound Semiconductor (CMOS) buffer circuit is planned. During this planned work, 45nm technology (VDSM) square measures implement new style of CMOS buffer with the mix PI section design of resistors and capacitors to boost the capability of CMOS buffer. The new model, verified by TSPICE simulations and measured information, includes delay, space and low power consumption result shows the higher performance rate of this planned system.*

**KEYWORDS:** CMOS, 32 nanometer technology, VDSM, Tspice.

## I. INTRODUCTION

Very-large-scale integration (VLSI) is that the method of making integrated circuits by combining thousands of transistors into one chip. VLSI began within the Seventies once advanced semiconductor and communication technologies were being developed. The microchip could be a VLSI device. VLSI became associate degree early trafficker of normal cell (cell-based technology) to the merchandiser market within the early 80s wherever the opposite ASIC-focused company, LSI Logic, was a frontrunner in gate arrays. VLSI's cell-based giving, the technology had been primarily accessible [2][16] solely inside massive vertically integrated corporations with semiconductor units like AT&T and IBM. Complementary metal-oxide- semiconductor (CMOS) could be a technology for constructing integrated circuits. CMOS technology is employed in microprocessors, microcontrollers, static RAM, and different digital logic circuits. CMOS technology is additionally used for many analog circuits [3] like image sensors (CMOS sensor), knowledge converters, and extremely integrated transceivers for several styles of communication. Frank Wanlass proprietary CMOS in 1963. CMOS is usually brought up as complementary- symmetry metal-oxide-semiconductor (or COS-MOS). The complementary- symmetry seek advice from the very fact that the everyday digital style vogue with CMOS uses complementary and symmetrical pairs of p-type and n-type Metal compound Semiconductor Field impact Transistors (MOSFETs) for logic functions. Consequently, CMOS devices don't turn out the maximum amount waste heat as different kinds of logic, as an example Transistor-Transistor Logic (TTL) or NMOS logic, that commonly have some standing current even once not dynamical state. CMOS additionally permits a high density of logic functions on a chip. It had been primarily for this reason that CMOS became the foremost used technology to be enforced in VLSI chips. Styles for a non-inverting CMOS buffer that drives a given load at 1GHz. the full circuit should [1] maintain noise margins higher than .5V, and should work inside an outlined

space. Most CMOS gates, inverters and high-current IC merchandise were unbuffered and exhibited smart logic-system performance, speed, noise immunity and quasi-linear characteristics in an exceedingly wide range of applications. Whereas initial buffered merchandise were confined to OR and AND functions, buffered NOR and NAND gates were introduced with constant generic 4000A-series designations because the original wide used unbuffered gates. Users were stunned by the non-interchangeability of the devices in applications wherever speed, noise immunity, output resistance, and linear gain-bandwidth characteristics were crucial. Its profit to CMOS users to possess accessible the definitions and designations of each [14] buffered and unbuffered. B-series CMOS devices as determined by the JEDEC CMOS Standardizing Committee underneath the cognizance of the JC40.2 JEDEC Committee of EIA. Comparisons of user-oriented characteristics and therefore the use of buffered and unbuffered gates are reviewed. A buffered CMOS device is one that the output ON resistance is freelance of any and every one valid input logic conditions, each preceding and gift is alleged to possess a buffered output or to be a buffered CMOS device.

### **1.1 Existing system**

The existing system, take into account Associate in Nursing overshooting result in nanoscale model, by together with the sub threshold region wherever the overshooting result seems. the most contribution is to review the result of overshooting result once applying 65nm technology to the model conferred. However it's noticed that the authors failed to take into account [9] the overshooting result that could be a vital physical facet and seems in nanometer regime of CMOS gate analysis. Associate in nursing analytical expression for nanoscale CMOS inverters is targeted during this system. Taking into thought the aspects that ought to be thought of, so the models in nanoscale maintain accuracy and to reduce the error share compared to plain simulators. Additionally to it, simplicity ought to be thought of to avoid heavy-weight computations. This content of the overshooting result caused a better error once smaller technologies square measure applied. If the overshooting, result that modifies the model by modeling this result as (Huang et al 2010) done to the model, that could be a vital from (Rosello and Segura 2011) in modeling submicron CMOS submicron gates.

### **1.2 Proposed method**

This system projected a thought of forty five nm CMOS buffer arrangements is enforced and additionally to scale back the delay rate of buffer output in low input power vary. Simulation output provides reduced delay performance in 45nm which supplies less time delay than existing sized CMOS. CMOS buffer within the variety of PI section electrical device and electrical condenser style based mostly projected CMOS equivalent circuit is enforced. Considering in account of delay, power consumption and space mistreatment 32nm technologies to implement the new variety of shift CMOS corresponding to style. For wide conductors with  $W$  &  $H$ , capacitance to substrate (of any ground plane) determined as a parallel plate electrical condenser  $C = \epsilon A/t$  wherever  $A$  is that the flattened space of the wire and  $t$  is that the thickness of the compound for many real conductors in these days. IC technology, fringing fields contribute a significant a part of the road capacitance and should be enclosed within the capacitance calculations. For  $W, W \sim H$ , fringing fields add quite the parallel plate portion to the overall line capacitance.

## **II. SYSTEM DESCRIPTION**

This project introduces a style for a non-inverting CMOS buffer that drives a given load at 1GHz. the entire circuit should maintain noise margins on top of .5V and should match at intervals an outlined space. Most CMOS gates, inverters and high-current IC merchandise were unbuffered and exhibited sensible logic-system performance, speed, noise immunity, and quasi-linear characteristics in a very large choice of applications [9]. Because the scope of CMOS merchandise broadened and extra manufacturer began creating them, buffered gate and electrical converter merchandise became obtainable. Whereas initial buffered merchandise area unit confined to OR and AND functions, buffered NOR and NAND gates area unit introduced with identical generic 4000A-series designations because the original wide used unbuffered gates.

## 2.1 Initial Design Concepts

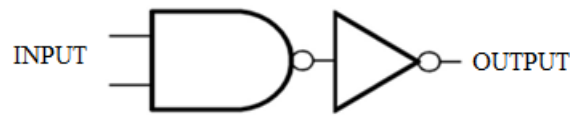


Figure 1 NAND to Inverter

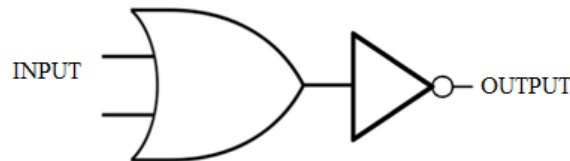


Figure 2 NOR to Inverter

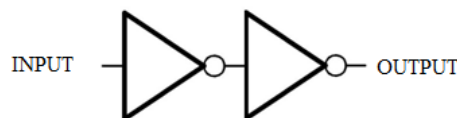


Figure 3 Inverter to inverter

The Figure 1 indicate the designs for the buffers include NAND neither to Inverter, Figure 2 indicate NOR to Inverter and Figure 3 indicate Inverter to Inverter. The NAND and NOR buffer implementation involve six total transistors, whereas the electrical converter to electrical converter style solely needs four transistors. The NAND and NOR styles add further space of two extra transistors, whereas the electrical converter to electrical converter style takes up a lot of less space with similar results for propagation delay and power dissipation [2]. For these reasons the electrical converter to electrical converter style best optimizes the figures of advantage. The higher limit to those values comes from constraint that the buffer junction transistor area remains below one hundred sq. microns. The lower limit happens once the dimension to length magnitude relation becomes too little and therefore the circuit isn't any longer able to swing rail-to-rail [5]. Therefore, the widths and parameters left to vary throughout the planning.

## 2.2 Analytical of buffer modeling

VLSI circuit analysis within the circuit level for the foremost vital measurements, like delay and power consumption depends on rigorous modeling of their basic parts [9]. One in every of the foremost prevailing and underlying parts in digital systems is that the CMOS buffer in Figure 4. A buffer may be a straightforward however principal and important part has several significant applications and it immensely used for signal cleanup and therefore the reduction of delay, noise and interference. This buffer is well-liked due to its low power consumption chiefly in shift phases. Hence, several researchers have self-addressed this want by proposing numerous analytical models to gift the behavior of CMOS buffers.

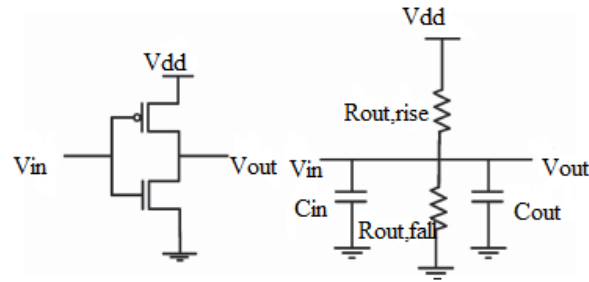


Figure 4 CMOS Buffer

Propagation time delay and power dissipation of buffer square measure its major factors that square measure sculpturesque. The time period once the output gets out of the steady-state price of the amplitude for the primary time is understood as overshoot time [1]. This parameter is presently one among the key parameters whereas managing buffers, since its equivalent to typical propagation delay of the buffer. The nonlinear operation of a MOS electronic transistor leads to nonlinear resistance and capacitance within the model. A closed-form expression to estimate the output resistances of a CMOS buffer is developed [6]. This methodology differs from the others within the means of the overshoot models have used the dynamic behavior equation of Associate in nursing electrical converter derived from Kirchhoff's Current Law (KCL) at the output node. In distinction, this new projected overshoot model is predicated on intuition and curve fitting, at the same time, still utterly in analytical kind.

### 2.3 Alpha power modeling

The Alpha-Power Law MOSFET Model is that the most generally used compact drain current model because of its straightforward mathematical kind and high degree of accuracy [8]. The model doesn't describe the sub threshold region and thus on/off drain current trade-offs can't be totally analyzed. The Low Power trans regional MOSFET model describes all regions of operation (sub threshold, triode, and saturation). Therefore, the Low Power Trans regional Model is associate degree advantageous selection for predicting performance of future technology generations and above all for analyzing on/off drain current trade-offs [6]. Coupling the Alpha-Power Law and Low Power Trans regional models permits a replacement compact physics primarily based Alpha-Power Law MOSFET Model. The three region model assumes that the output current may be a linear performs of the input voltage. This can be truly solely the case for a totally speed saturated device. For a tool with no speed saturation this may be a perform of the sq. of the input voltage [12]. Most up-to-date devices have fall time, somewhere in between these two extremes. This can be taken into consideration by introducing a brand new curve fitting parameter  $\alpha$  and writing the output current as follows:

$$I_{out}(t) = \min \left( \frac{(V_{in}(t) - V_T) \alpha W}{R_M} \cdot \frac{V_{out}(t) W}{R_F} \right) \quad 1 \leq \alpha \leq 2 \quad (1.1)$$

In this approach utilized by Nabavi-Lishi is termed the alpha-power law model. a similar input wave kind is assumed for the three region model  $V_{out}(t)$  Power consumption, space and delay area unit resolved within the same means [12]. The employment of  $\alpha$  within the expression for current is that the solely initial assumption that is completely different from the three region model. For the case wherever  $\alpha = 1$  the alpha-power law model is a dead ringer for the three region model. Once approximating delays to  $VDD=2$  ( $\Delta V_{out} = \text{zero.5}$ ) the result most frequently falls within the linear region. Therefore, the easy approximation the opposite two regions area unit unnoticed and also the linear region equation is employed alone.

$$I_D \approx \frac{T_{in} (\alpha + V_T)}{1 + \alpha} + \frac{T_M \Delta V_{out}}{1 - V_T} \quad (1.2)$$

This single equation and the three region approximation given in equation are simply the sum of two terms. One proportional to the input slew time and one proportional to the capacitive load. For any value of  $\alpha$  only difference between these equations values of  $V_T$  and  $R_M$  used to fit a given set of data. Therefore, when using this single equation approximation the alpha-power law model and the

three region model are identical [9]. The three region approximation (which is identical to the alpha-power law approximation) is a simple equation with only two curve fitting parameters ( $V_T$ ,  $R_M$ ). Like the two region model is takes into account and input slope to provide better accuracy.

## 2.4 Accurate power model

In VDSM, the physicist semiconductor unit model isn't any longer valid. This happens as a result of short channel effects like quality degradation, drain elicited barrier lowering, and speed saturation [9]. Therefore, so as to accomplish a much better analysis, a lot of correct model is needed. A traditional CMOS buffer is created of NMOS and PMOS transistors, as delineate. For temporal arrangement analysis, of these model parts should be averaged in time once the signal transits between two low and high values. The particular in operation regions (linear or saturation) within the quantity rely on the kind of load driven by the buffer. During this temporary, we've supposed a pure electrical phenomenon load, for NMOS and PMOS transistors of the buffer. At the start of the rising input, the PMOS semiconductor unit is within the sub threshold region. The result of this current is hefty in VDSM CMOS technologies.

## III. SYSTEM ARCHITECTURE

The system architecture is following in figure 5

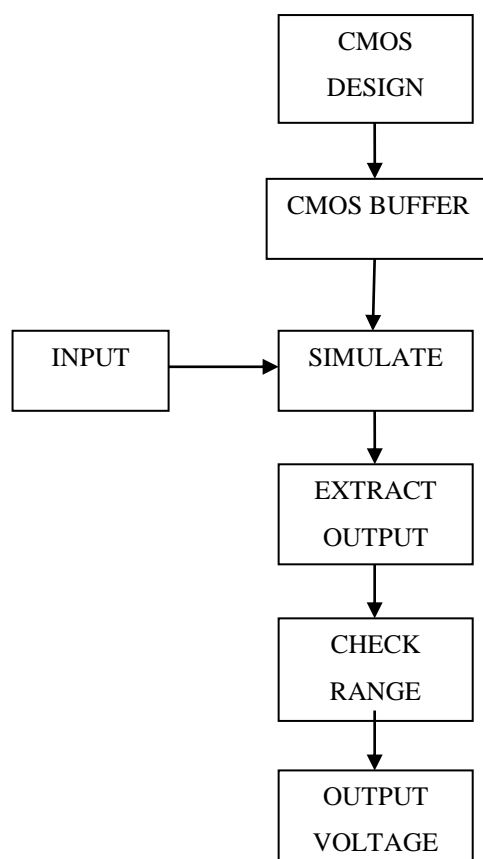


Figure 5 System Architecture

### 3.1 32 NM Technology

A low-power “32” nm technology could be a continuation of the joint development initiative between Samsung manufactory and JDA alliance partners [5]. Various products from high fables players are in production since 2008 enabled by 32nm low power method technology and its style scheme. The 32nm method is characterized by many key technologies, that offers 193nm immersion lithography patterning of important style rules with radial asymmetry rates cherish dry litho systems. Also, suggests immoderate Low-K nonconductor materials for metal line insulation leading to RC delay reduction vs. low-k. Increasingly, for semiconductor makers moving to advanced nodes – 90nm, 65,

45 and below the best challenge is lithography. This is often as a result of lithography is essentially affected by basic principles of optical physics. At 65 nm, a line is a smaller amount than a third of the effective wavelength because the business moves forward; optical phenomenon and interference have become elementary obstacles, not simply second order effects [15]. It's long been familiar that the simplest lithography that's on paper potential may be achieved by considering the look of ion masks as Associate in nursing inverse downside so finding the inverse downside to seek out the best ion mask for a given method, employing a rigorous mathematical approach. Inverse Lithography Technology (ILT) has been explored for several years. Though these early approaches to ILT usually resulted in very good lithography, they're usually impractical in an exceedingly production setting. Runtimes area unit several order of magnitude too slow, and therefore the ensuing masks area unit usually too complicated to manufacture.

**IV. RESULT AND ANALYSIS**

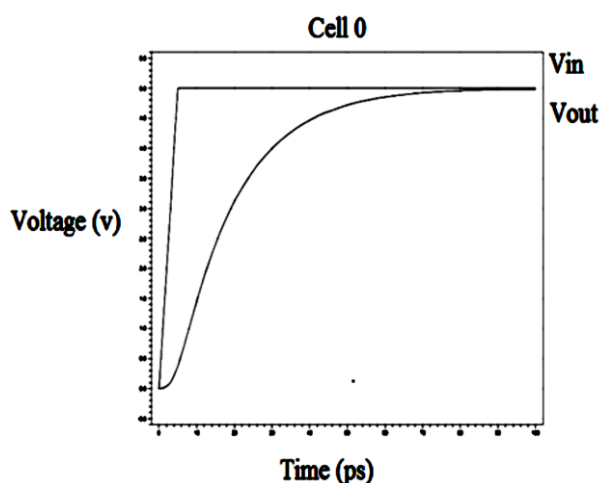


Figure 6 Delay waveform

Time delay for 2 CMOS

Buffer in series = absolute (time taken for i/p signal - Time taken for o/p signal)  
 = abs (18-34) psec  
 = 16 psec

For single buffer = 8 psec

The area size comparison is given in following Table 1

Tech Node (nm)	Physical Gate (nm)	Tox (nm)	K	V <sub>th</sub> (V)	Na/ (cm <sup>3</sup> )	Nd/ (cm <sup>3</sup> )
130	90	3.0	3.7	0.34	1.0e16	1.0e19
90	53	2.4	3.0	0.32	1.4e16	1.4e19
65	32	1.7	2.5	0.29	2.0e16	2.0e19
45	22	1.5	2.0	0.29	2.9e16	2.9e19
32	12	1.2	1.7	0.28	3.0e16	3.0e19

Table 1 Comparison of area size

The comparison of delay and power consumption is given in following table 2

	130 NM	90 NM	65 NM	45 NM	32 NM
DELAY	15.4 Psec	13.3 psec	11.2 psec	9.5 psec	8 psec
POWER	6.124mW	5.186 mW	2.277 mW	0.692 mW	0.541mW
VOLTAGE	1.2v	1.1v	0.9v	0.8v	0.5v

Table 2 Comparison of delay and voltage

## V. CONCLUSION

Power dissipation has been reduced and propagation delay has been optimized throughout the planning of CMOS buffer driving massive electrical phenomenon hundreds. The short power and sub-threshold leak power are decreased to scale back total power dissipation in deep submicron (DSM) region. During this project, implement PI section primarily based electrical device and capacitance combination circuit for CMOS buffer style. During this structure extract the higher result than ancient buffer circuit. Here analyze the performance of projected system for the output voltage at every instant.

## VI. FUTURE SCOPE

Using BDSM technology to scale back the world, delay and power consumption for CMOS buffer improve to 32nm technology. With the scaling of CMOS technology into the terribly deep sub micrometer (VDSM), buffer modeling has been a essential demand thanks to its several appearances within the style and analysis of digital systems. CMOS buffer within the type of PI section electrical device and electrical condenser style primarily based projected CMOS equivalent circuit is enforced. Considering in account of overshoot impact, the new type of shift CMOS equivalent style is enforced.

## VII. APPLICATIONS

- 1) Microprocessors
- 2) Microcontrollers
- 3) Static RAM and Digital logic circuit
- 4) Several analog circuits like Image sensors, knowledge converters and extremely integrated Transceivers.

## REFERENCES

- [1] Abedalsalam, B. (2011) "The Impact of Modeling the Overshooting Effect in sub threshold region for Nanoscale CMOS Inverter", International Conference on Innovations in Information Technology, pp. 205–225.
- [2] Ajay, S., Khare, D., Anurag, G. and Sanjay, V. (2012) "LLP in Chain Inverter by using CMOS Circuit", International Journal of Scientific Engineering and Technology Vol. 5, No. 4, pp. 71-75.
- [3] Darren, B. and Thomas, B. (2005) "A New Non-Quasi-Static Non-linear MOSFET Model Based on Physical Analysis", Department of Electronic and Electrical Engineering, 13th symposium, pp. 304-308.
- [4] Harmander, S., Rahul, R., Kanak, A., Dennis, S. and Richard, B. (2010) "Dynamically Pulsed MTCMOS With Bus Encoding for Reduction of Total Power and Crosstalk Noise", IEEE Transactions on very large scale integration (VLSI) systems, Vol. 18, No. 1, pp. 522–531.
- [5] Joel, H. and Bogda, W. (2011) "SPICE as a Fast and Stable Tool for Simulating a Wide Range of Dynamic Systems", International Journal of Engineering Education Vol. 27, No. 2, pp. 217–224.
- [6] Keith, B., Blanca, A., John, E., Xinghai, T. and James, M. (2012), "A Physical Alpha-Power Law MOSFET Model", Semiconductor Research Corporation in Solid-State Circuits, Vol. 22, No. 1, pp. 433–448.
- [7] Magdy, M., and Eby, F. (2004) "Optimum wire sizing of RLC interconnect with repeaters", Department of Electrical and Computer Engineering, Integration, the VLSI journal 38, pp. 205–225.
- [8] Marco, B., Lucia, G., Raimondo, L., Pasquale, T., and Alessandro, T. (2003) "A High-Speed IC Random-Number Source for SmartCard Microcontrollers", IEEE Transactions on circuits and systems fundamental theory and applications, Vol. 50, No. 11, pp. 400–401.
- [9] Milad, M., Mohammad, H., Mazaheri, K., Nasser, M. and Reza, S. (2013) "New Approach to VLSI Buffer Modeling, Considering Overshooting Effect", IEEE Transactions on very large scale integration (VLSI) systems, Vol. 21, No. 8, pp. 2816–2823.
- [10] Milos, S., Alexandre, S. and Yusuf, L. (2010) "Selective Redundancy-Based Design Techniques for the Minimization of Local Delay Variations", IEEE Transaction of Microelectronic Systems Laboratory, Vol. 61, No. 15, pp. 388–396.
- [11] Tim, G. and Mohammed, B. (2010) "692-nW Advanced Encryption Standard (AES) on a 0.13 $\mu$ m CMOS", IEEE Transactions on very large scale integration (VLSI) systems, Vol. 18, NO. 12, pp. 1477–1486.
- [12] Usha, G., Jesús, A. and Christopher, P. (2010) "RF Power Potential of 45 nm CMOS Technology", IEEE Transaction on IBM Microelectronics, Vol. 18, No. 1, pp. 615–626.

- [13] Yangang, W. and Mark, Z. (2009) “Analytical Transient Response and Propagation Delay Model for Nanoscale CMOS Inverter”, IEEE Transactions on very large scale integration systems Vol. 6, No. 2, pp. 1410–1414.
- [14] Zakir, H. and Quazi, K. (2013) “Threshold Voltage Roll-off Due to Channel Length Reduction for a Nanoscale n-channel FinFET”, International Journal of Emerging Technologies in Computational and Applied Sciences (IJETCAS), pp. 152- 156.
- [15] Zhangcai, H., Atsushi, K., Masanori, H., Takashi, S., Minglu, J. and Yasuaki, I. (2010) “Modeling the Overshooting Effect for CMOS Inverter Delay Analysis in Nanometer Technologies”, IEEE Transactions on computer-aided design of integrated circuits and systems, Vol. 29, No. 2, pp. 110–115.
- [16] Introduction about VLSI [online]. Available: <http://baslerweb/>
- [17] Bhattacharyya, A. (2000) “PREDICTMOS MOSFET Model and its Application to Submicron CMOS Inverter Delay Analysis”, IEEE Transactions on Very large scale integration, Vol.14, No.5, pp. 210-216.
- [18] Dipanjan, S. and Resve, S. (2009) “Power-Delay Metrics Revisited for 90nm CMOS Technology”, Proceedings of the Sixth International Symposium on Quality Electronic Design, pp.302-308.